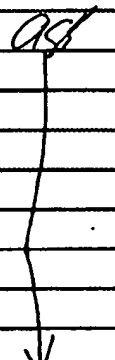
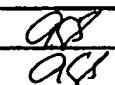
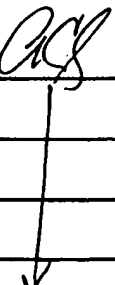
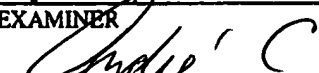


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				APPLICANT Badri N. KRISHNAMURTHY et al.			
				FILING DATE August 14, 2001		GROUP 2812	
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

4